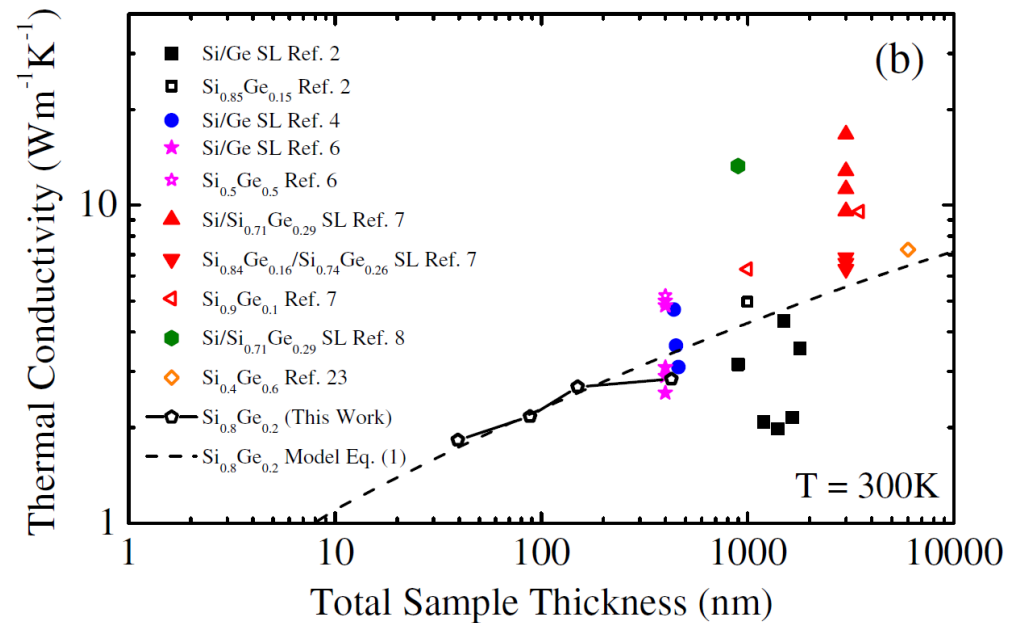
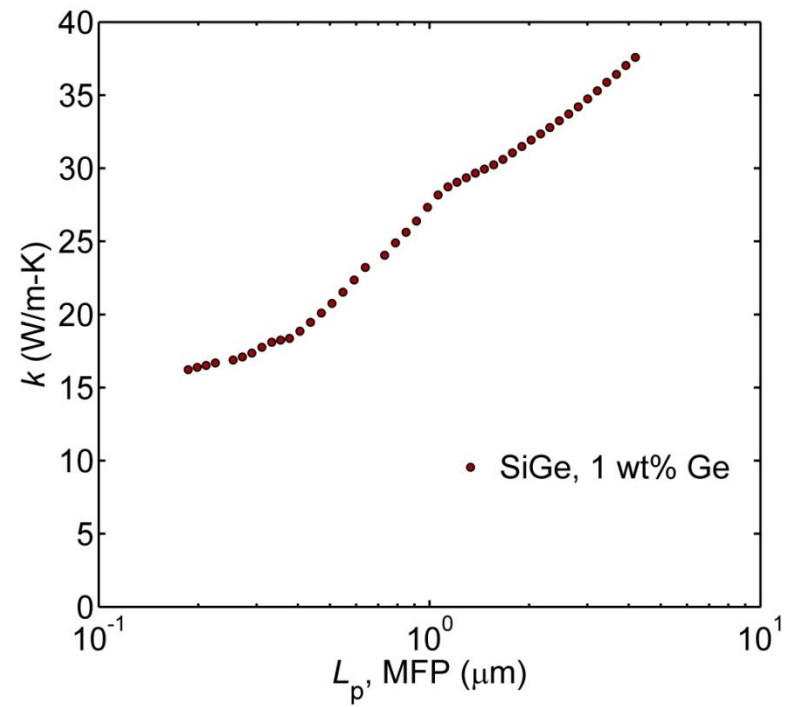
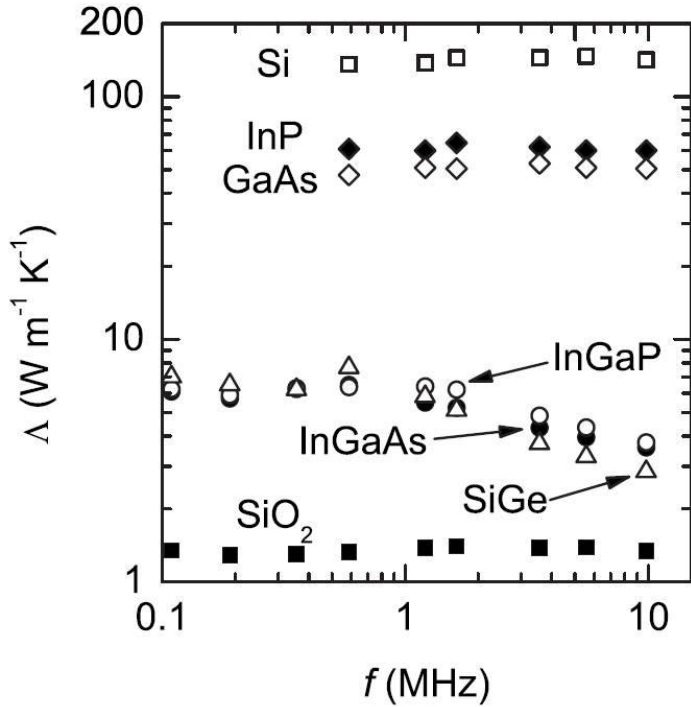


Evidence for propagating modes in alloys and amorphous solids

Discussion with Jason and Keith
February 8, 2013

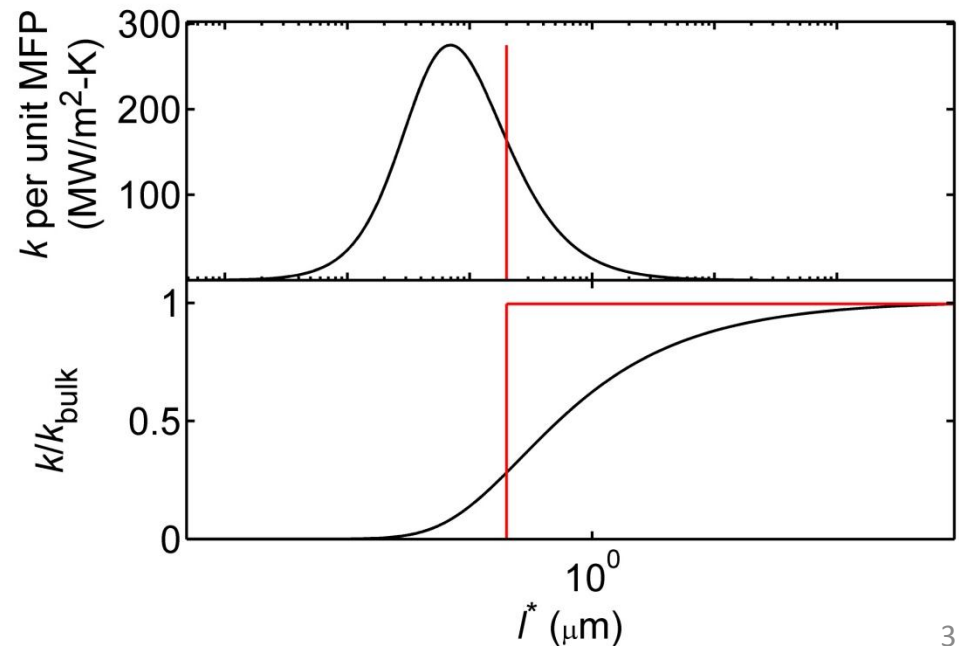
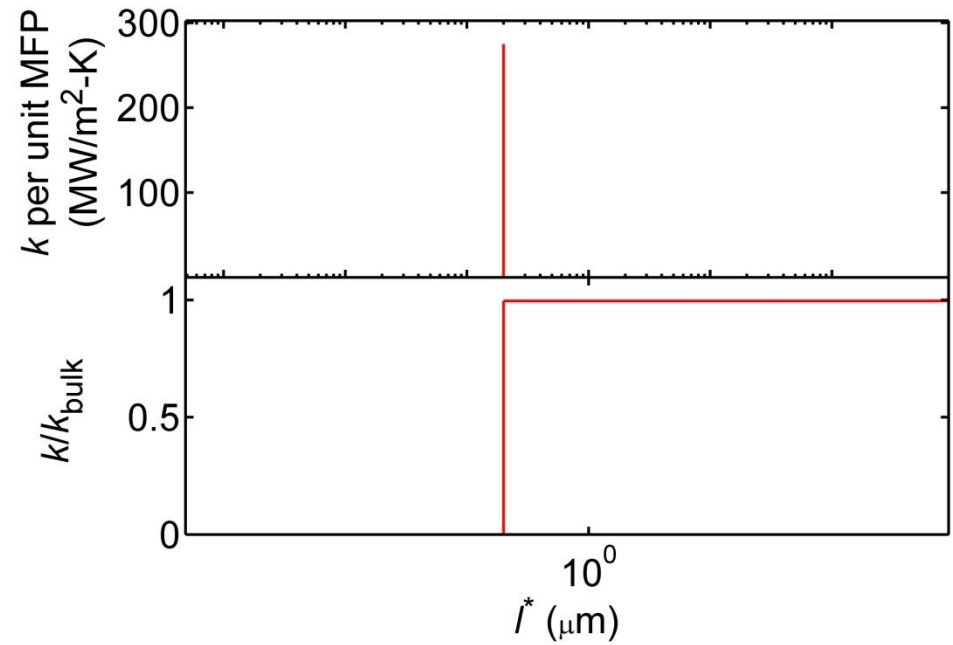
SiGe measurements



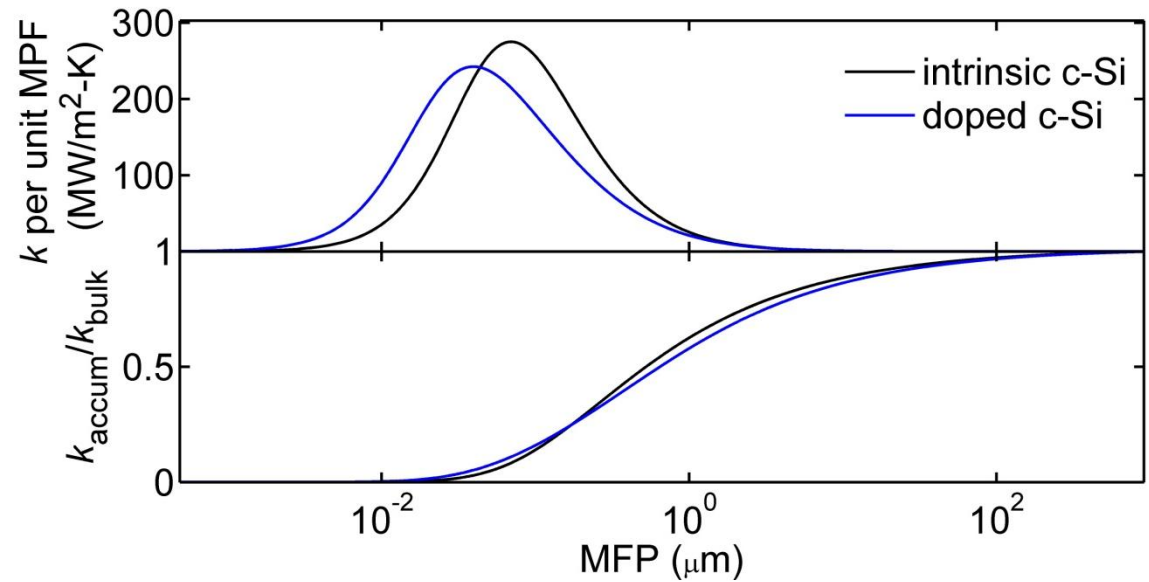
accumulation function

$$l_{\text{bulk, Si}} = \frac{3k}{\int C v d\omega} = 225 \text{ nm}$$

Distribution from the ω dependence
of phonon scattering

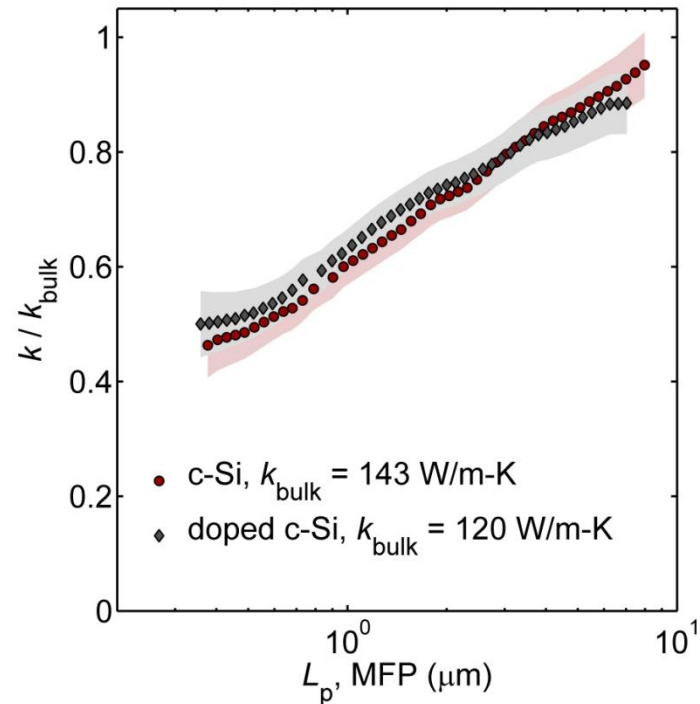


intrinsic vs. doped Si



We would expect that impurity scattering should reduce MFPs

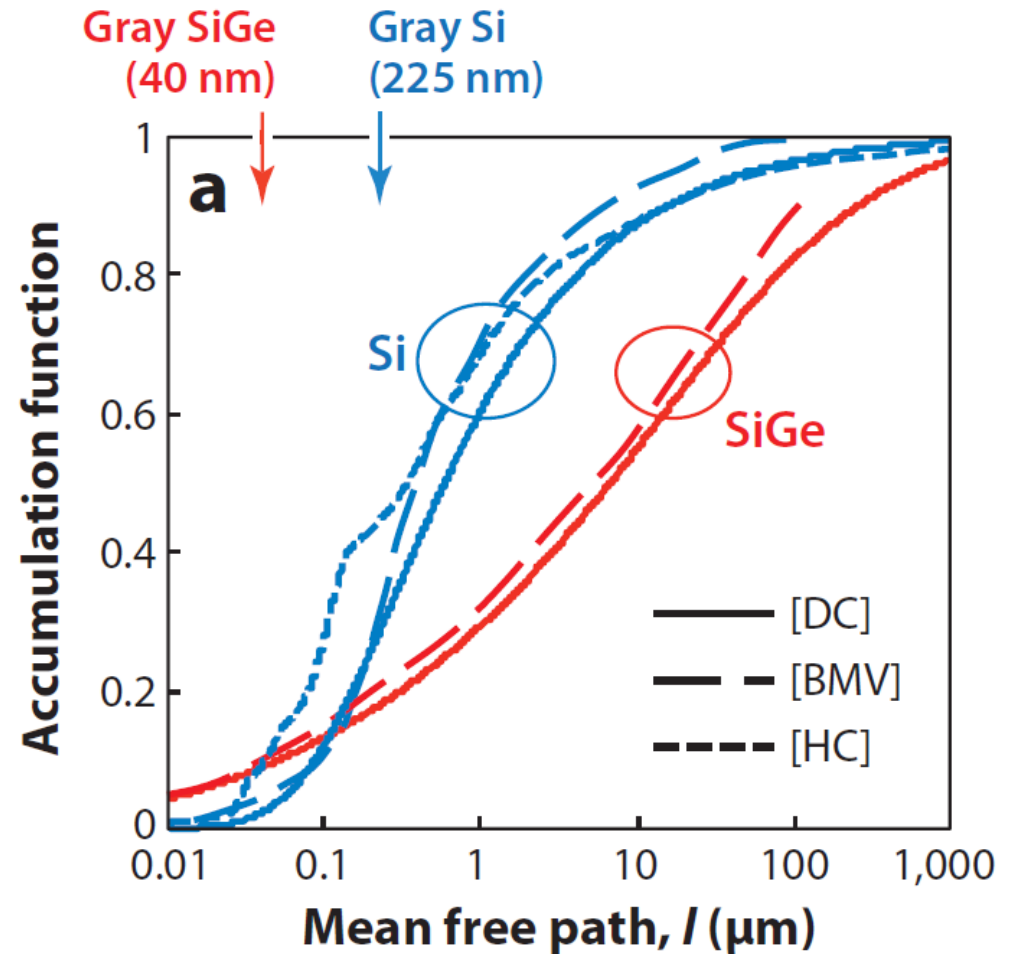
MFP spectrum in doped Si is broader than that of crystalline Si???



SiGe alloy

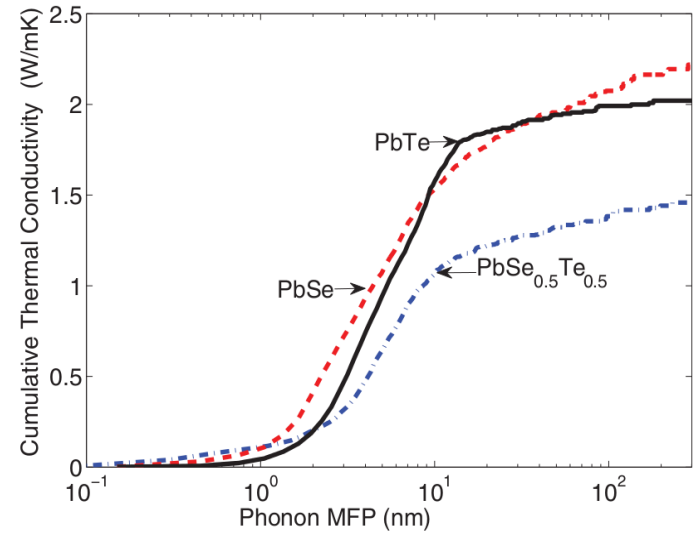
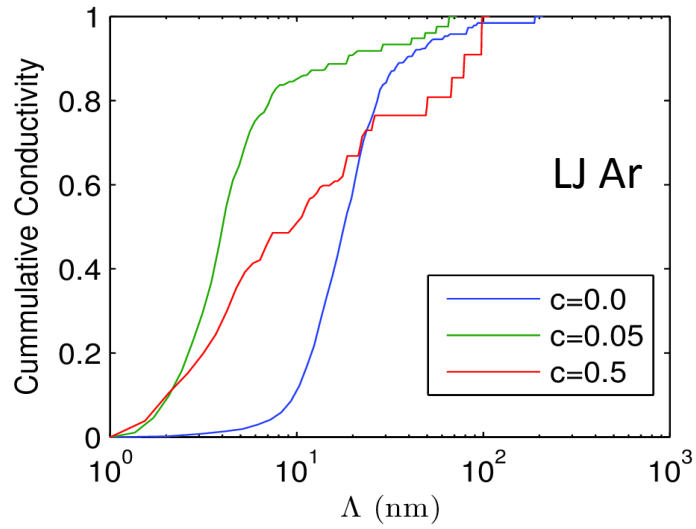
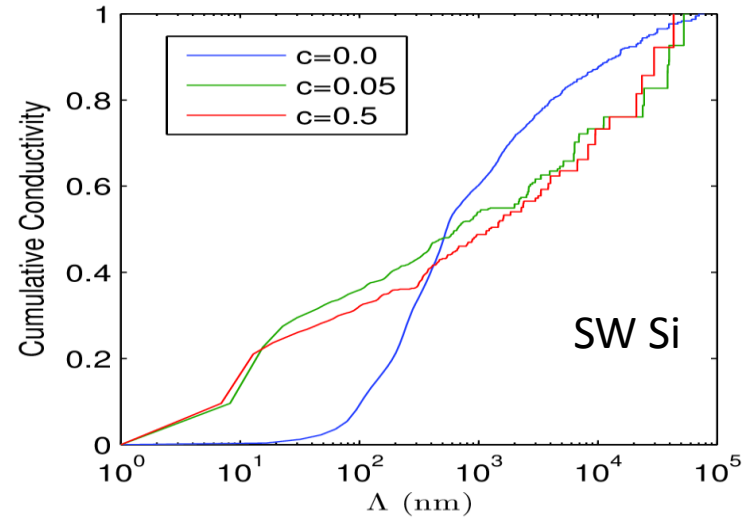
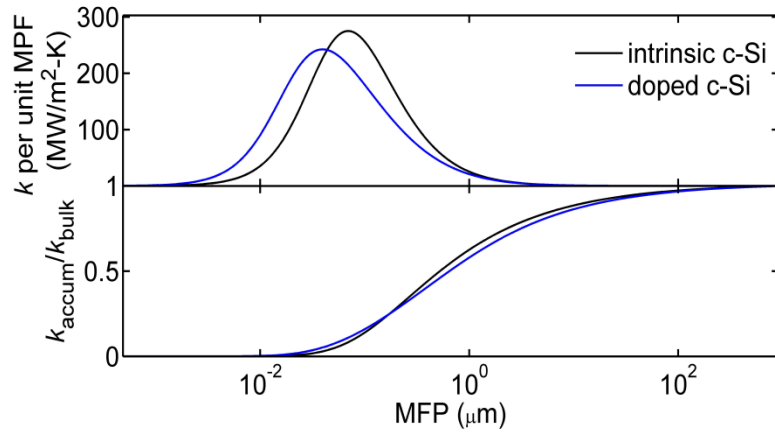
$$l_{\text{bulk, Si}} = \frac{3k}{\int C v d\omega} = 225 \text{ nm}$$

$$l_{\text{bulk, SiGe}} = \frac{3k}{\int C v d\omega} = 40 \text{ nm}$$



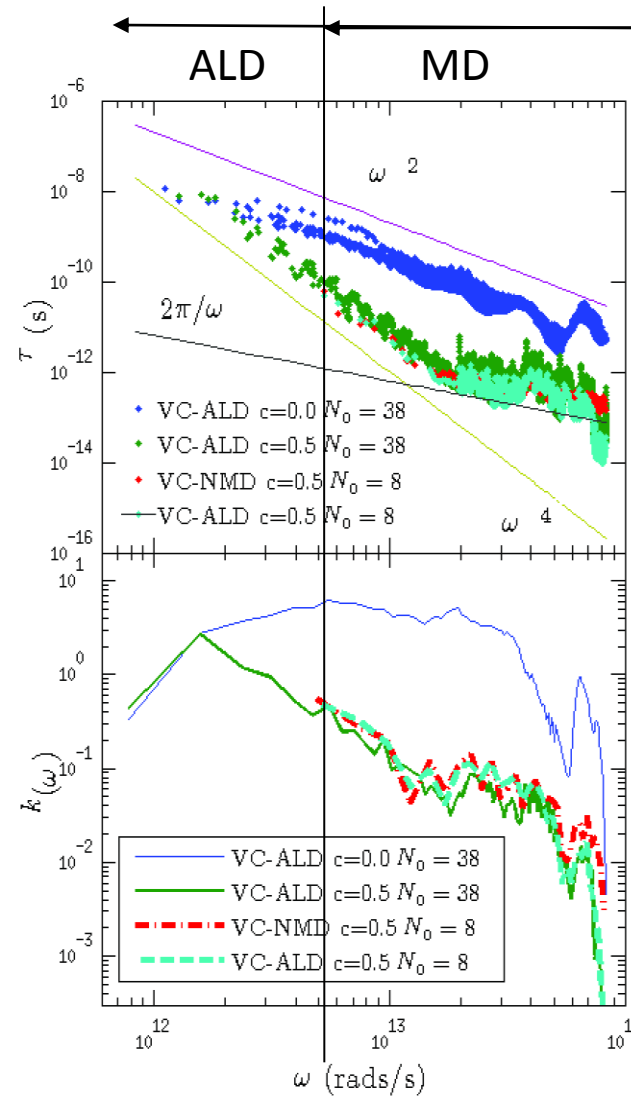
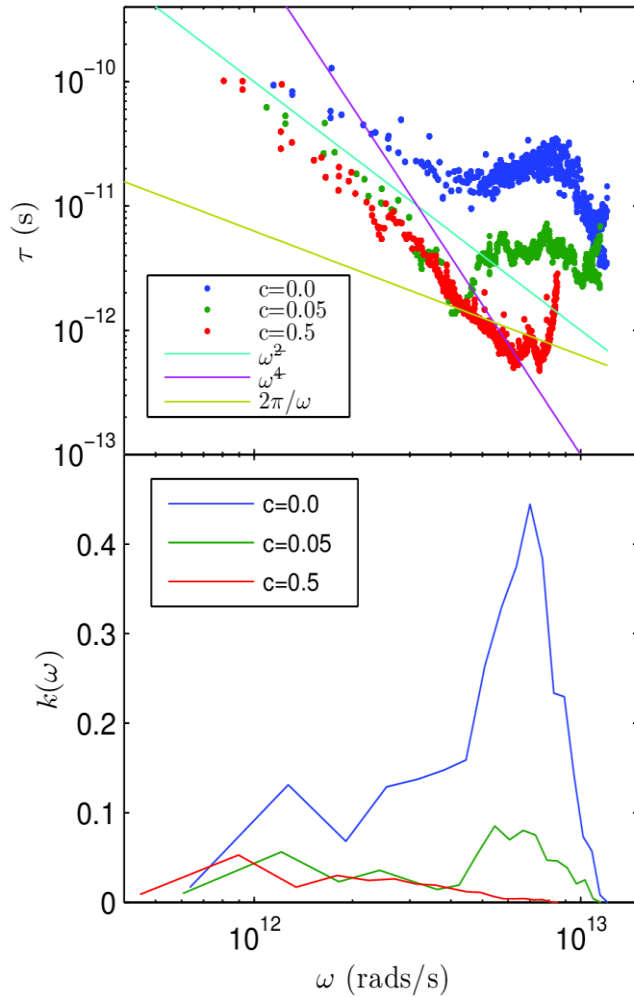
Defects strongly suppress short λ phonons (high ω), the phonons remaining to contribute to k are now biased towards longer λ (lower ω), which skews the distribution towards longer MFP phonons

conductivity accumulation



Phonon spectrum: LJ Ar vs. SW Si

MD



MD-based:

1E4 modes

(7 days)*(100 cpu)

ALD:

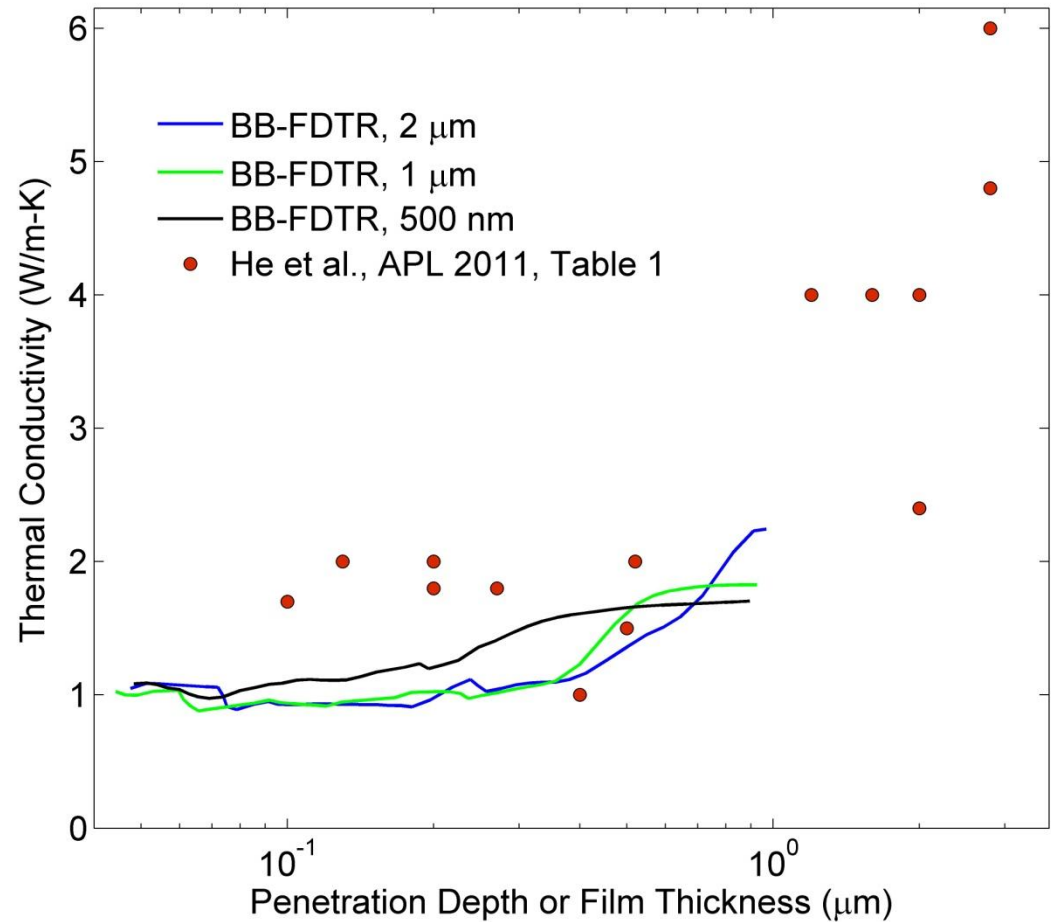
1E6 modes

(7 days)*(12 cpu)

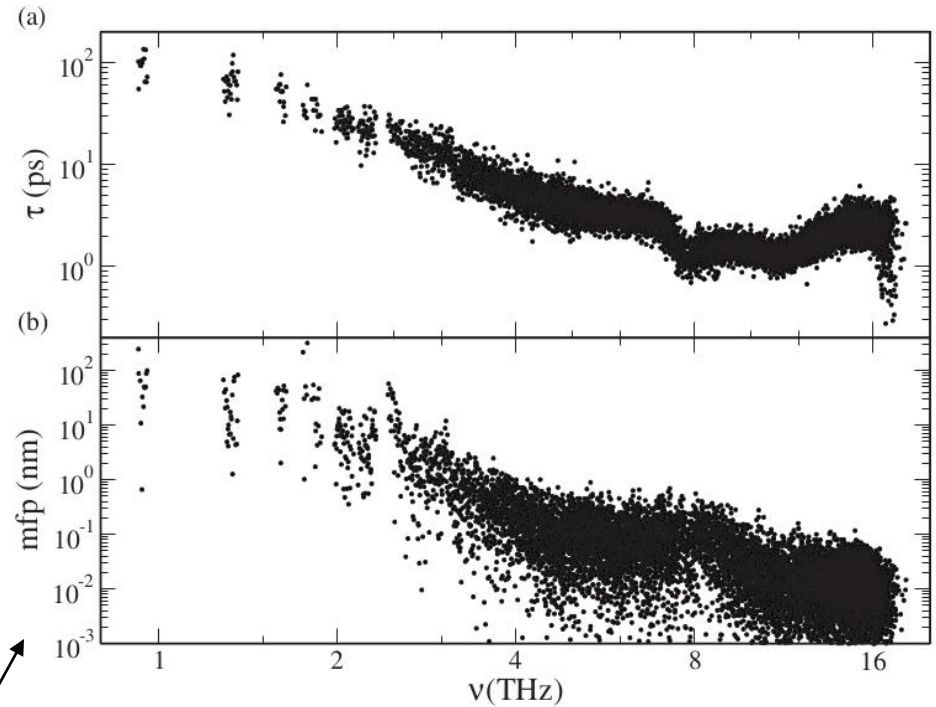
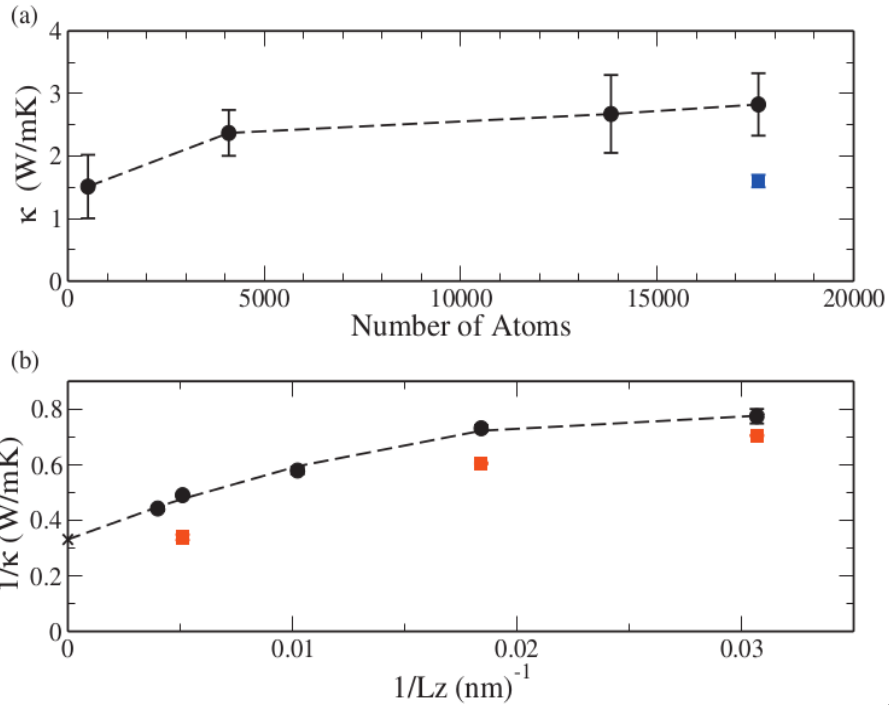
amorphous Si measurements

Is there some inherent lower limit on the MFP that is greater than zero?

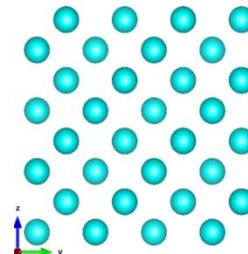
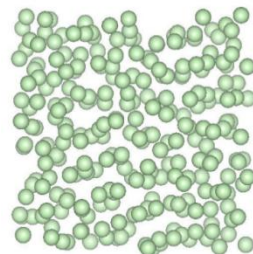
Does it even make sense to talk about MFP within this plateau?



MFP in a-Si from Tersoff and MD



MD-based: size of simulation cell=4.3 nm



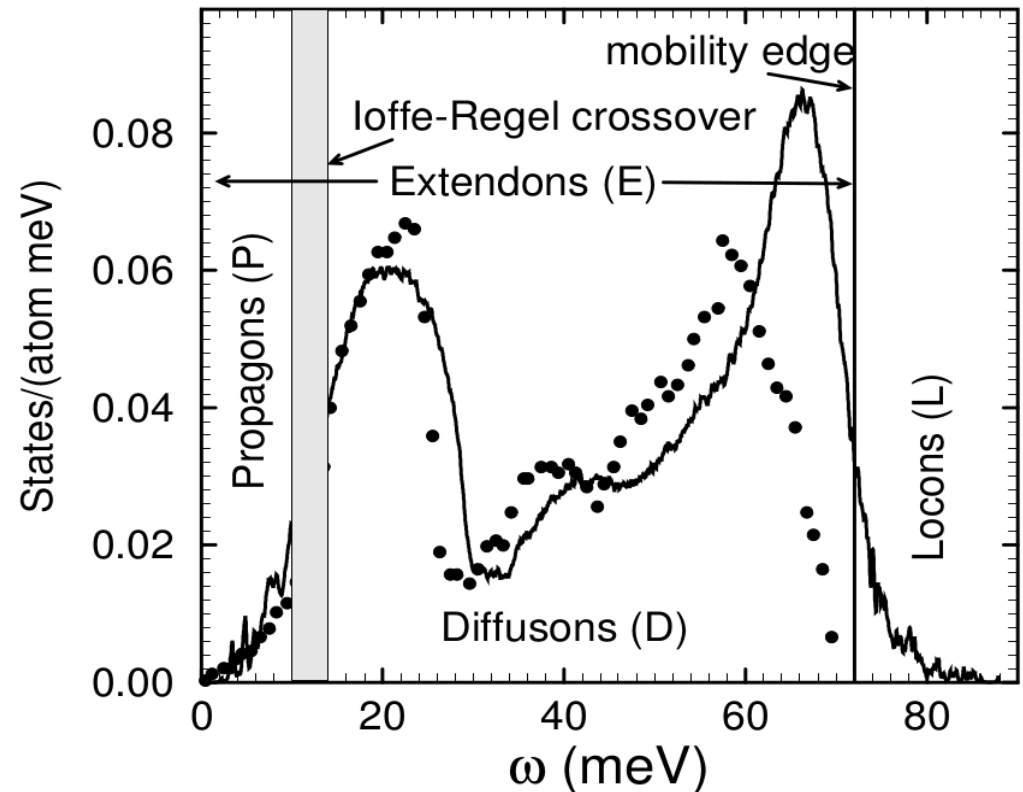
propagons, locons, diffusons

Numerical studies of amorphous silicon show that the lowest 4% of vibrational modes are plane-wave like, “propagons”

the highest 3% of modes are localized, “locons”

The rest are neither plane-wave like nor localized, “diffusons”

vibrons $\left\{ \begin{array}{l} \text{extendons} \\ \text{locons} \end{array} \right\}$ $\left\{ \begin{array}{l} \text{propagons} \\ \text{diffusons} \end{array} \right\}$



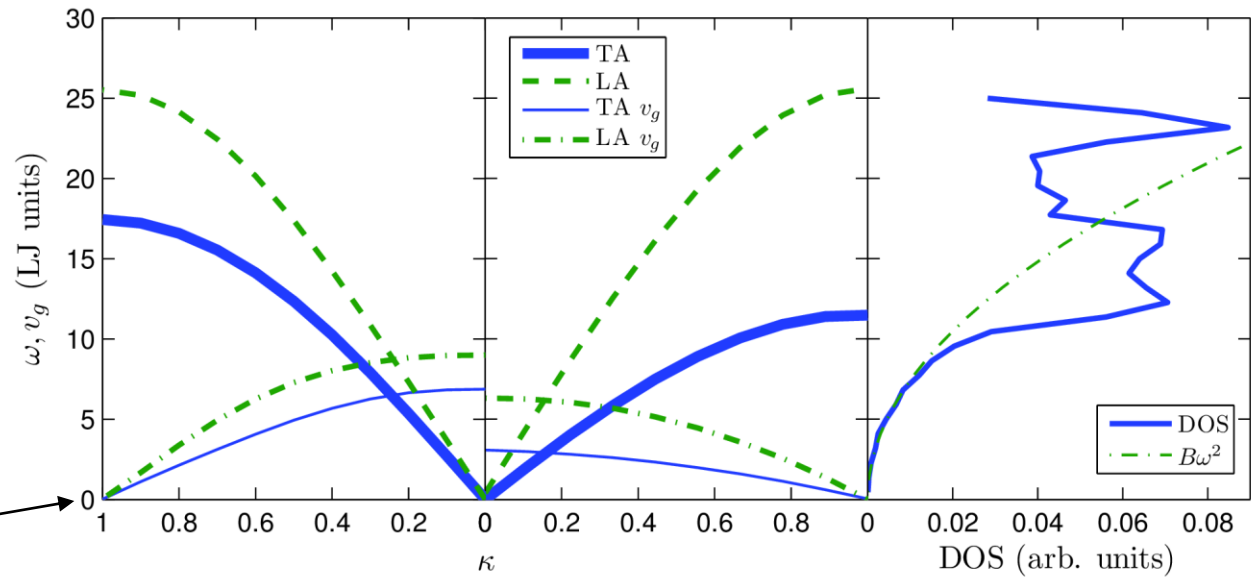
ordered and disordered

$$k_{ph,\mathbf{n}} = \sum_{\mathbf{\kappa}} \sum_{\nu} \frac{k_B}{V} \mathbf{v}_{g,\mathbf{n}}^2(\nu) \tau(\nu) \quad v_{g,\mathbf{n}}(\nu) = \partial \omega(\nu) / \partial \mathbf{\kappa}$$

$$D_{ph}(\mathbf{\kappa}) = \mathbf{v}_g^2(\mathbf{\kappa}) \tau(\mathbf{\kappa})$$

$$\Lambda(\mathbf{\kappa}) = |\mathbf{v}_g| \tau(\mathbf{\kappa})$$

$$D_{ph}(\mathbf{\kappa}) \approx 0 \rightarrow$$

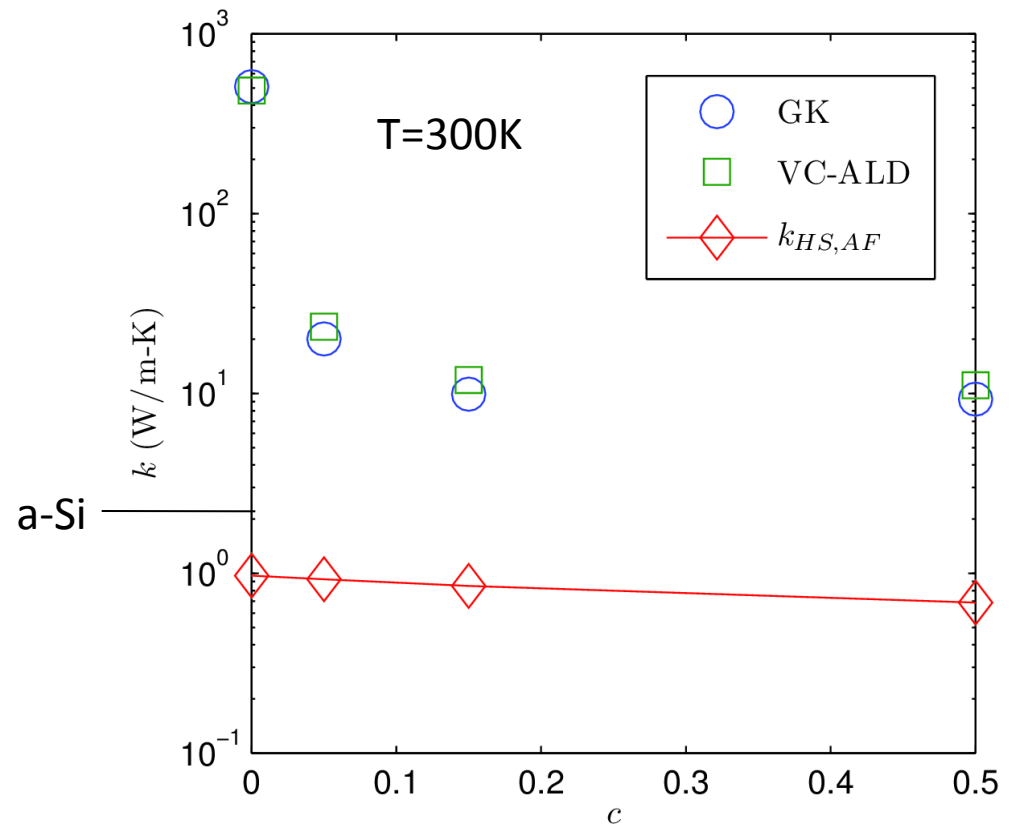


In a disordered material, it is not possible (in general) to specify v_g and τ independently

$$k_{AF} = \sum_{modes} \frac{k_B}{V} D_{AF}(\omega(\mathbf{\kappa}_{\nu}=\mathbf{0}))$$

high-scatter limit: SW Si

$$k_{AF,HS} = \frac{k_B}{V_b} b v_s a$$



high-scatter limit: LJ Ar

$$k_{AF} = \sum_{modes} \frac{k_B}{V} D_{AF}(\omega(\kappa=0))$$

$$k_{AF,HS} = \frac{k_B}{V_b} b v_s a$$

